



US Department of Commerce Patent and Trademark Office Form PTO-1449 (Modified)		Atty. Docket No.: 42390P11370		Application No.: 09/965,280			
		Applicant: Ohfuji et al.					
		Filing Date: September 26, 2001					
US Patent Documents							
Examiner's Initials		Date	Document Number	Name	Class	Sub- Class	Filing Date
Foreign Patent Documents							
Examiner's Initials		Date	Document Number	Country	Class	Sub- Class	Translation
Other Documents (Including Author, Title, Date, Pertinent Pages, etc.)							
<i>SRM</i>		Alexei L. Bogdanov, Use of SU-8 Negative Photoresist for Optical Mask Manufacturing MAX-Lab, University of Lund, SE-221 00, Lund Sweden. [online] Pages 1-11. http://www.maxlab.luy.se/beamlines/bld811 . Proc. SPIE Vol. 3999. Pub. 2000.					
<i>SRM</i>		SPIE Volume 2512; Masumi Arai, Hiroyuki Inomata, Toshiharu Nishimura, Masa-aki Kurihara and Naoya Hayashi; "Application of Chemically Amplified Resists to Photomask Fabrication". Micro Products Research Laboratory, Micro Products Division, Dai Nippon Printing CO., Ltd., Japan. Pages 74-87. Pub. 1995.					
<i>SRM</i>		SPIE Volume 2793; A Chemically Amplified Resist Process For 0.25 u M Generation Photomasks; Mikio Katsumata, Hiroichi Kawahira, Minoru Sugara and Satoru Nozawa. MOS LSI Division, Semiconductor Company, Sony Corporation, Japan. Pages 96-104. Pub. 1996.					
Examiner <i>Mohamedulla</i>				Date Considered <i>3/15/05</i>			

Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw a line through the citation if not in conformance and not considered. Include a copy of this form with the next communication to the applicant

* Did not receive any NPLs.